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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Justin K. Brask et al.

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Art Unit: 2811

Serial No.: 10/626,336

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Examiner: Ori Nadav

Filed: July 24, 2003

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Atty Docket: ITL.1022US
P16709

For: Forming a High Dielectric Constant
Film Using Metallic Precursor

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Assignee: Intel Corporation

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Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed March 30, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: April 18, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L Hayden
Cynthia L. Hayden